

SUPPORT FOR THE AMENDMENTS

The amendments to the claims are supported by the specification. Accordingly, no new matter is believed to have been added to the present application by the amendments submitted above.

REMARKS

Claims 1-8 are pending. Favorable reconsideration is respectfully requested.

The present invention relates to a process for producing a carbon-containing SiO₂-containing insulating layer on chips, wherein at least one silicon compound selected from the group consisting of (1) alkylarylalkoxysilanes, (3) C₁- and C₃-C₅ alkyl orthosilicates, (4) orthosilicates having glycol radicals, (5) orthosilicates having polyether radicals, (7) hydrogenaryloxysilanes, (8) alkyl-hydrogensilanes, (9) alkylhydrogenalkoxysilanes, (10) dialkylhydrogenalkoxysilanes, (11) arylhydrogensilanes, (12) arylhydrogenalkoxysilanes, (13) acetoxysilanes, (14) silazanes, (15) siloxanes, (16) organofunctional silanes bearing at least one acetoxo, azido, amino, cyano, cyanato, isocyanato or ketoximato group, (17) organofunctional silanes containing at least one heterocycle, with the silicon atom being able to belong to the heterocycle itself or be covalently bound to the heterocycle, (18) mixtures of at least two silicon compounds described above and (19) mixtures of tetraethoxysilane with at least one silicon compound described above, is used as precursor. See Claim 1.

The rejection of the claims under 35 U.S.C. §102(b) over Levert is respectfully traversed. This reference fails to suggest the claimed process for producing a carbon-containing SiO₂-containing insulating layer on chips.

As noted in the Office Action, Levert discloses an aryltrialkoxysiloxane. In the amendment submitted above, that embodiment has been removed from the claims.

In view of the foregoing, Levert fails to disclose the claimed process for producing a carbon-containing SiO₂-containing insulating layer on chips. Accordingly, the subject matter of the pending claims is not anticipated by that reference. Withdrawal of this ground of rejection is respectfully requested.

The rejections of the claims under 35 U.S.C. §102(b) and §103(a) over Mitchener alone or in view of Smith are respectfully traversed. These references fail to disclose or suggest the claimed process.

The Examiner cites trimethoxysilane and triethoxysilane. However, those compounds are believed to not be within the scope of Claim 1 and have been removed from Claim 3.

In view of the foregoing, Mitchener alone or in view of Smith fails to disclose or suggest the claimed process. Accordingly, the subject matter of the pending claims is not anticipated by or obvious over those references. Withdrawal of this ground of rejection is respectfully requested.

Regarding the Restriction Requirement, Applicants request that the withdrawn claims be rejoined. The withdrawn claims depend from Claim 1. Since Claim 1 is allowable for the reasons described above, the withdrawn claims are allowable as well.

Applicants submit that the present application is in condition for allowance. Early notice to this effect is earnestly solicited.

Respectfully submitted,

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